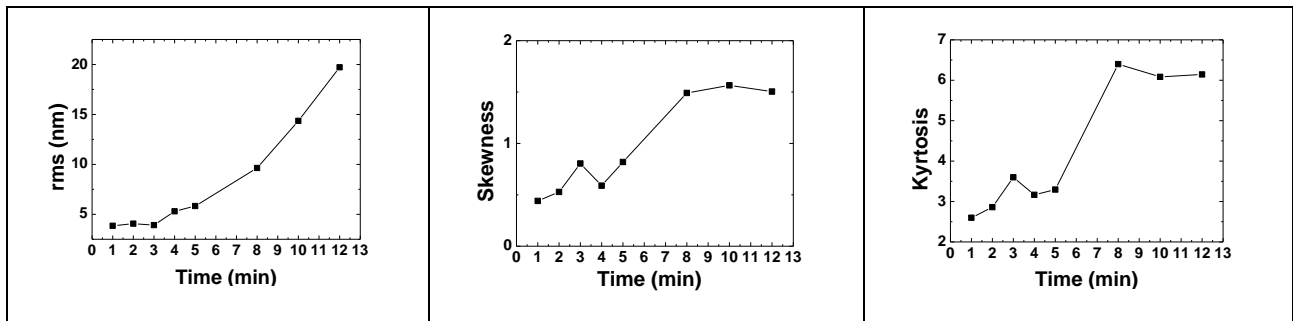




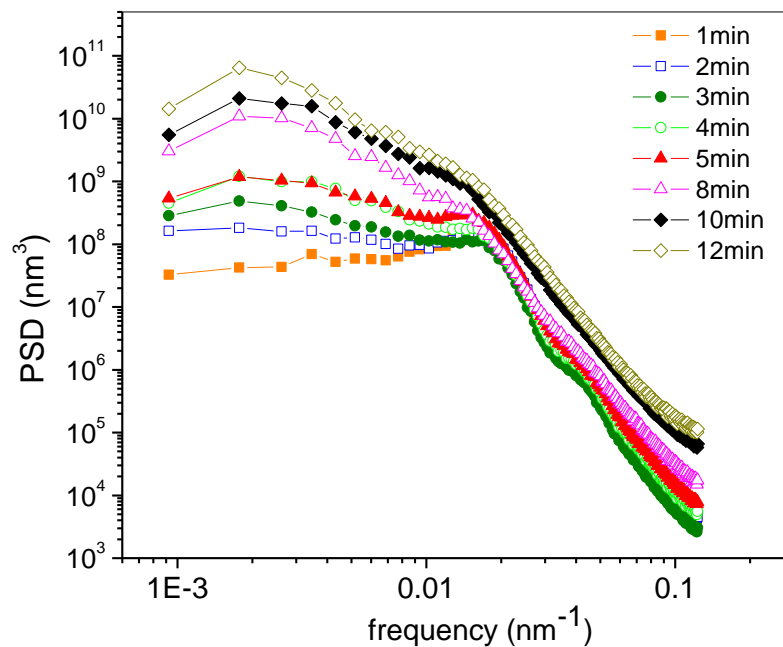




frequency. This power law quantifies in frequency terms the emergence of the second scale topography associated with low frequency fluctuations in surface morphology.



**Figure 4.** Evolution of the surface morphology metrics with oxygen plasma etching time. Vertical roughness parameters are shown versus time: rms (a), skewness (b) and kyrtnosis (c).



**Figure 5.** Circularly averaged Power Spectral Density (PSD) of etched surfaces versus etching time. Notice the importance of low frequency at long etching times, and the transition taking place between 5min and 8min of etching.

**References:**

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